

# Accepted Manuscript

Locating Si atoms in Si-Doped Boron Carbide: a Route to Understand Amorphization Mitigation Mechanism

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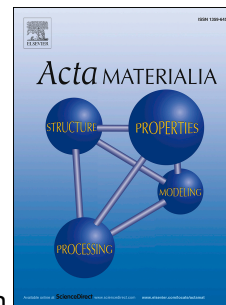
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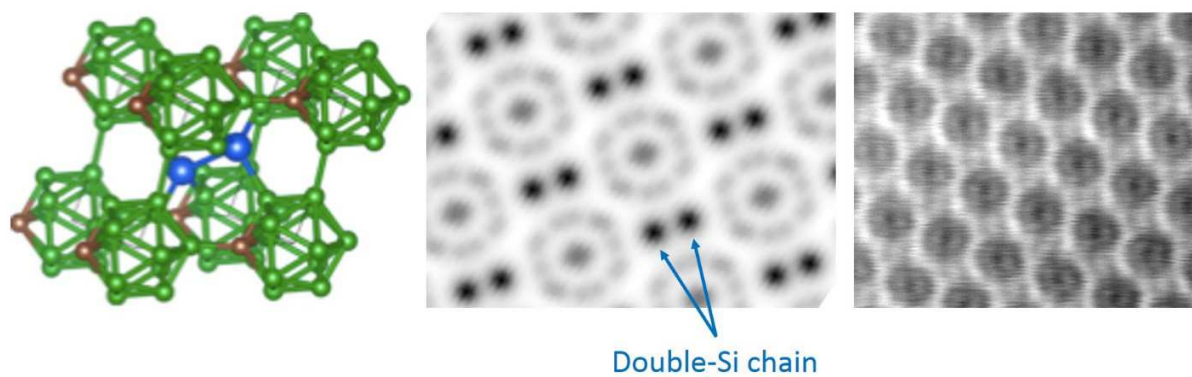
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(a) Simulated Model    (b) Simulated ABF image    (c) Actual ABF image



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